

**Amendments to the Specification:**

Please replace the paragraph beginning at page 27, line 4, with the following amended paragraph:

Since phosphorus is not added in portions shielded with the resist masks 1116 and 1117, the second impurity regions 1114 and 1115 remain at the portions as they are. Thus, the second impurity region 1114 was defined. At the same time, the third impurity region 1119 was defined so that an edge of the gate insulating film 1118 is aligned with a boundary between the second impurity region 1114 and the third impurity region 1119.